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"electronic additions" (i.e. surface adatoms or vacan-

Previous studies of GaAs(001) surfaces [17]

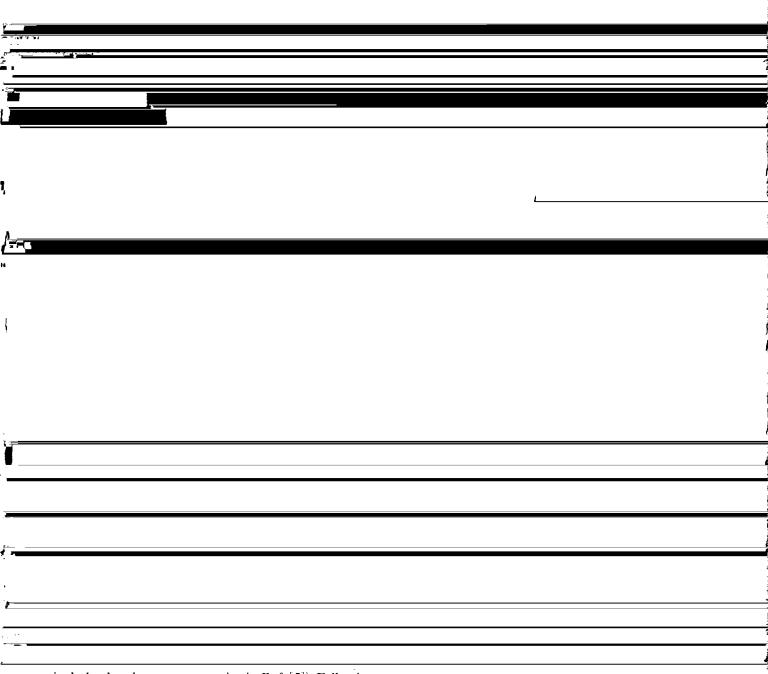
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stable and semiconducting flat surfaces. While step-step interaction has noticeable effects on step formation energies, the formation of steps is generally endothermic. There are two commonly observed steps: those with edges received the direction of surface As motifs, leading to a set of point charges on various surface atoms. For example, Ga has 3 valence electrons, so fourfold coordinated $Ga^{(4)}$ contributes 3/4 electrons to each of its four bonds. This leads to local charge neutrality. Planer $Ge^{(3)}$ is $a^{-2}/4$ electron donor

4.2. Stahility of A stens vs B stens

Acknowledoments

As mentioned in Section 3.4, Heller et al. [5] have measured step energy by way of measuring the kink distribution on $GaAs(001)-2 \times 4$. Depending on temperature, they obtained an A step formation energy We would like to thank S. Froyen for many helpful discussions on the subject. This work was supported by the Office of Energy Research (Division of Materials Science of the Office of Basic Science), US Department



include also the corner energies in Ref. [5]). Following Heller et al., one may derive from the calculated kink energy in Section 3.4 the A step formation energy. This gives $28-31 \text{ meV}/(1 \times)$. Heller et al. also determined the B:A energy ratio to be 5.6–6. Ide et al. [7], on the contrary, estimated the ratio from measured aniso-

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